Fig. 3
Residual polymers unstripped

OCO 35096 THE RECK REMANDED

Fig. 4 After stripping with 100 ppm of H_2SiF_6

Fig. 5 After stripping with 500 ppm of H_2SiF_6

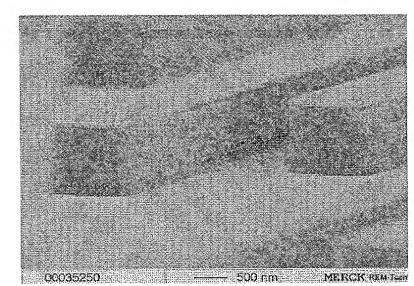


Fig. 6 After stripping with 1000 ppm of H_2SiF_6

10

10

00033090 500 mm MERCK REM-IVER

20

25

30

Fig. 7
After stripping with 100 ppm of HF

00035140 — SOO mm MERCK REMJand

Fig. 8
After stripping with 200 ppm of HF

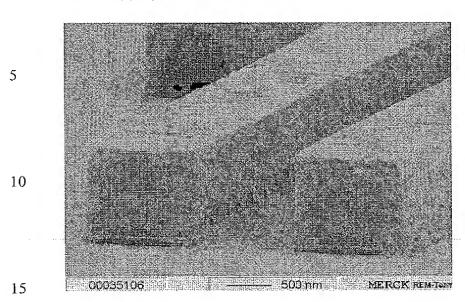


Fig. 9
After stripping with 500 ppm of HF

Stripping results in a Mattson AWP tank processor with various $H_2 \mathrm{SiF}_6$ concentrations.

Fig. 10
After stripping with 100 ppm of H₂SiF₆

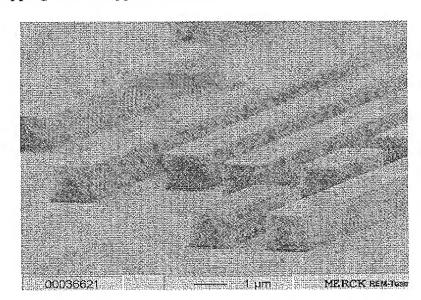


Fig. 11 After stripping with 600 ppm of H_2SiF_6

Fig. 12: Result after use of a composition with added surfactant.

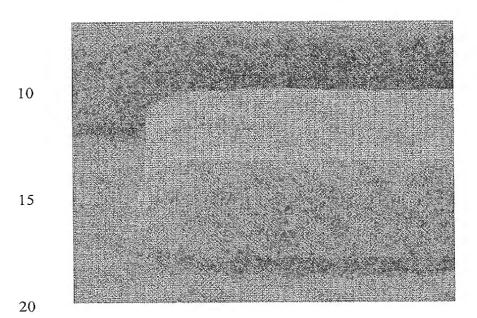


Fig. 13
Comparison with Fig. 12: Result after use of a composition without added surfactant.

